

MARKED-UP SPECIFICATION

Please rewrite the sentence beginning on page 3, line 15 as --

In one embodiment, the second layer is Hydrogen [Hydroxy] Silsesquioxane.

Please rewrite the sentence beginning on page 6, line 10 as --

Materials appropriate for forming layer 130 include Hydrogen [Hydroxy] Silsesquioxane (SiO_x ; where x is less than 2).

MARKED-UP CLAIMS

9. (Amended) The photolithographic mask of claim 1, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.

16. (Amended) The photolithographic mask of claim 15, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.

36. (Amended) The photolithographic system of claim 35, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.